Supporting Information

Regioselective Alkyne Polyhydrosilylation: Synthesis and Photonic Properties of Poly(silylenevinylene)s


†Fok Ying Tung Research Institute, The Hong Kong University of Science & Technology (HKUST), Nansha, Guangzhou, China, ‡Department of Chemistry, HKUST, Clear Water Bay, Kowloon, Hong Kong, China, #State Key Laboratory of Supramolecular Structure and Materials, Jilin University, Changchun, 130012, China, ξThe Institute of Textiles and Clothing, The Hong Kong Polytechnic University, Hunghom, Kowloon, Hong Kong, China, and §Department of Polymer Science and Engineering, Zhejiang University, Hangzhou 310027, China

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**Figure S2.** (A) PL spectra of P3/6 in THF and THF/water mixtures with different water fractions. (B) Change in the relative PL intensity ($I/I_0$) with the composition of the THF/water mixture. Concentration: $10^{-5}$ M; excitation wavelength: 350 nm.

**Figure S3.** (A) PL spectra of P4/6 in THF and THF/water mixtures with different water fractions. (B) Change in the relative PL intensity ($I/I_0$) with the composition of the THF/water mixture. Concentration: $10^{-5}$ M; excitation wavelength: 350 nm.
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Figure S9. Wavelength dependence of refractive index of thin films of P2/6. Data for the thin film of P2/6 after UV irradiation for 15 min at room temperature are denoted as P2/6*.

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